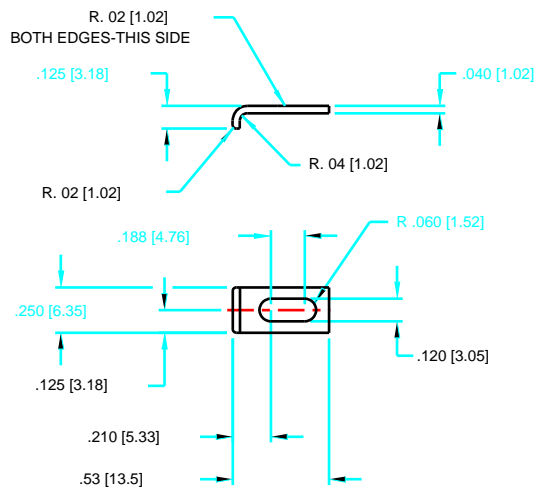


( B )	PLOT SCALE: 2=1	DWG. SCALE: .5	A2335800
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# NOTES:

- THIS IS A ULTRA- HIGH VACUUM COMPONENT (UHV)
- WHEN MACHINING VACUUM PARTS, USE SILICONE AND SULPHUR-BASED CUTTING FLUIDS IS PROHIBITED. USE ONE OF THE FOLLOWING:
  - CIMCOOL 5 STAR 49
  - TRIM SOL
- THIS IS A UHV PART, ELECTROPOLISHING IS NEEDED. PRIOR TO ELECTROPOLISHING, THE PART NEEDS TO GO THROUGH A MULTIPLE STEP CLEANING PROCESS INVOLVING DEGREASING, WASHING AND DRY NITROGEN BLOWDOWN.
- KEEP THE PART CLEAN AND WRAP FOR UHV PACKING WITH ALUMINUM FOIL.
- DIMENSIONS IN [ ] ARE MILLIMETERS AND FOR REF. ONLY
- SURFACE ROUGHNESS  $\sqrt{63}$

SYM	CHANGE DESCRIPTION	BY	CHKD	DATE
	REVISIONS			



ITEM	DWG/PART NUMBER	NOMENCLATURE OR DESCRIPTION	MATERIAL / SPEC	QTY
<p>UNLESS OTHERWISE SPECIFIED LOG NUMBER ALL DIMENSIONS ARE IN INCHES TOLERANCES</p> <p>DECIMALS ANGULAR            .1 .03            .01 .01            .005 .005</p> <p>SURFACE ROUGHNESS <math>\sqrt{63}</math>            REMOVE ALL BUMPS AND            BREAK SHARP EDGES AS MAX.            SURFACE TEXTURE TO BE IN            ACCORDANCE WITH LATEST ASH            AND TOLERANCES IN            ACCORDANCE WITH LATEST ASH</p> <p>DO NOT SCALE DRAWING</p>				
A2335800		<p>THIS DRAWING IS THE PROPERTY OF  <b>ARGONNE NATIONAL LABORATORY</b></p> <p>DESIGNED BY J.GOGOL DATE 9/14/95            CHECKED BY            DESIGNED J.GOGOL DATE 9/14/95            RESPONSIBLE ENGINEER</p> <p>CHIEF DESIGN ENGINEER DATE            OP. LEADER            PROJECT MGR.            APPROVED/RELEASED</p> <p>TITLE  <b>ADVANCED PHOTON SOURCE</b></p> <p>X1-84 2ND CRYSTAL HOLDER            FOR 3-ID-A KOHZU            RETAINER</p>		
MATERIAL: 304 STAINLESS STL		SCALE 2:1	SHEET 1 of 1	SIZE B
		DRAWING NUMBER P4105091103-840006-00		